

Notice of References Cited	Application/Control No. 10/604,244	Applicant(s)/Patent Under Reexamination TAI ET AL.	
	Examiner Toan M Le	Art Unit 2863	Page 1 of 1

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	C	US-6,477,432	11-2002	Chen et al.	700/51
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	M	US-			

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NON-PATENT DOCUMENTS

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	V	Scher et al., In-line Statistical Process Control and Feedback for VLSI Integrated Circuit Manufacturing, IEEE 1989, Pages 70-75.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.